

Neuromorphic pilot lines and new material systems for storage technologies

Neuromorphic ecosystem in QNC

- Heterogeneous technology landscape bridges the gap between materials science and CMOS production
- Cross-partner cooperation enables application-oriented evaluation of new storage technologies and material systems
- Industry-oriented production environments enable accelerated transfer



Pilot production at wafer level 2

Early points of contact with external production environments Focusing the partners on different abstraction levels of technology development (material - storage - accelerator)



New material systems for storage technologies 3

Integration of ferroelectric **Synapses and Neurons based on Ferroelectric Devices AIScN layers in CMOS and III-V** technologies P-channel N-channel LTD LTP LTP LTD 120-2 μs (n) 140· 2 μs Η +t +**0.9** V 200 nm 100-+0.4 V 25%~75% Bereich innerhalb von 1.5IQR ¹ 2 μs -0.3 V Medianlinie 100 TiN Mittelwert Ausreiße 1E-5 - programmed at 40 V HZO/SiN NiSi erased at -50 V $V_D = -0.5 V$ $V_{\rm D} = -0.5 \, {\rm V}$ NiSi SiO 1E-6 40 60 80 100 40 60 80 Pulse Number 20 100 20 0 10 20 V_G [V] Pulse Number 50 52.5 55 56 58 59 60 61 62 63 64 65 66 67 68 69 70 -20 -10 V_p in V Synapse with n-Channel Fe-SBFET Synapse with p-Channel Fe-SBFET Memory window of AIScN-based BEOL-FeFETs and Ferroelectric Schottky FET Holes as neurotransmitters **Electrons as neurotransmitters** multilevel statistics for increasing write pulse amplitudes V_{DD} Sensing Inverter 1 Inverter 2 V_{SENSE} ≥0.5 ≤ 0.5-SENSE 1_____ 10 15 15 20 Time (ms) 25 10 Time (ms) 0.0 0.5 Voltage [V] Distance [pm] 5 Fe-SBFETs Thalamus Neuron Tonic mode (LiF) Burst Mode bottom Pt electrode — 5 nm

Micro- and nanoscale

A. Grenmyr, J. Zhang, K. Moto, Y.-T. Liao, D. Grützmacher, Q.-T. Zhao, Adv. Funct. Mater., under review

Scaling of the layer thickness of ferroelectric AIScN layers in the sub-10nm range and structural characterization of a domain wall

memristors based on 2D materials (e.g. MoS2, h-BN)



Schematic representation and implementation of a boron nitride memristor in a crossbar with nickel electrodes [3].



switch-on ($V_{th,on}$) and switch-off point (Vth_{off}) statistics of elements of a crossbar [3].

[3] L. Völkel, et al, Resistive Switching and Current Conduction Mechanisms in Hexagonal Boron Nitride Threshold Memristors with Nickel Electrodes. Adv. Funct. Mater. 2024, 34, 2300428. doi: 10.1002/adfm.202300428





- Establishment of a development path from material systems to neuromorphic accelerators
- Harmonization of characterization methods for a uniform benchmark of new, promising approaches
- Increased development speed through the use of synergies







MemMeasure board for transient characterization memristive components for neuromorphic circuits





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